

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Confirmation No.: 6655

First Named Inventor

: Hiroshi SHINRIKI : October 3, 2003

Filed

: 1762

TC/A.U. Examiner

: B. P. Chen

: 10/678,045

Docket No.

: 010986.52822US

Customer No.

: 23911

Title

: Removing Oxide Film on a Substrate with Hydrogen

and Fluorine Radicals

## **LETTER**

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

It is the understanding of the undersigned, after speaking with Examiner Chen of the U.S. Patent and Trademark Office earlier this morning, Friday, April 28, 2006, that this case is now in condition for allowance.

Respectfully submitted,

April 28, 2006

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